

**INFORMATION DISCLOSURE  
CITATION IN AN  
APPLICATION**



(PTO-1449)

ATTY. DOCKET NO.  
**49657-961**

SERIAL NO.  
**09/769,490**

APPLICANT  
**Kenji ITOGA, et al.**

FILING DATE  
**January 26, 2001**

GROUP  
**2882**

**U.S. PATENT DOCUMENTS**

| EXAMINER'S<br>INITIALS | PATENT NO. | DATE       | NAME   | CLASS | SUBCLASS | FILING DATE |
|------------------------|------------|------------|--------|-------|----------|-------------|
| <i>K</i>               | 4634643    | 01/06/1987 | SUZUKI | —     | —        | —           |
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| EXAMINER'S<br>INITIALS | PATENT NO.           | DATE                  | COUNTRY                     | CLASS        | SUBCLASS     | Translation  |              |
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|                        |                      |                       |                             |              |              | Yes          | No           |
| <i>K</i>               | 8-152499             | 06/11/1996            | Japan (w/ English Abstract) | —            | —            |              | X            |
| <i>K</i>               | 0 597 664 A2         | 05/18/1994            | EPO                         | —            | —            |              | X            |
| <i>K</i>               | <del>4,634,643</del> | <del>01/06/1987</del> | <del>SUZUKI</del>           | <del>—</del> | <del>—</del> | <del> </del> | <del> </del> |
| <i>K</i>               | 0 597 664 A2         | 05/18/1994            | EPO                         | —            | —            |              | X            |
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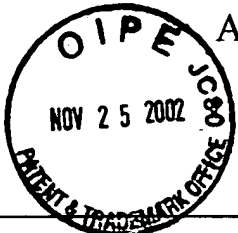

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| <i>K</i> | "Laser Generated X-Ray Source for Time-Resolved Biological and Material Structure Studies",<br>BARTUNIK et al., Structural Biological Applications of X-Ray Absorption, Scattering, and<br>Diffraction, pp. 331-348, 1996 |
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| <b>INFORMATION DISCLOSURE<br/>CITATION IN AN<br/>APPLICATION</b><br><br><br>(PTO-1449) |                                                                                                                                                                                                                                                                |      |         | ATTY. DOCKET NO.<br><b>49657-961</b>    |          | SERIAL NO.<br><b>09/769,496</b> |    |
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| <b>U.S. PATENT DOCUMENTS</b>                                                                                                                                            |                                                                                                                                                                                                                                                                |      |         |                                         |          |                                 |    |
| EXAMINER'S<br>INITIALS                                                                                                                                                  | PATENT NO.                                                                                                                                                                                                                                                     | DATE | NAME    | CLASS                                   | SUBCLASS | FILING DATE                     |    |
| <b>FOREIGN PATENT DOCUMENTS</b>                                                                                                                                         |                                                                                                                                                                                                                                                                |      |         |                                         |          |                                 |    |
| EXAMINER'S<br>INITIALS                                                                                                                                                  | PATENT NO.                                                                                                                                                                                                                                                     | DATE | COUNTRY | CLASS                                   | SUBCLASS | Translation                     |    |
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| <b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>                                                                                                 |                                                                                                                                                                                                                                                                |      |         |                                         |          |                                 |    |
|                                                                                                                                                                         | "X-Ray nanolithography-the clearest path to 0.1 and sub-0.1um ULSI", M.L. Schattengurg et al, JJAP Series 5, Proc. of 1990 Intern. MicroProcess Conference, pp. 63-70.                                                                                         |      |         |                                         |          |                                 |    |
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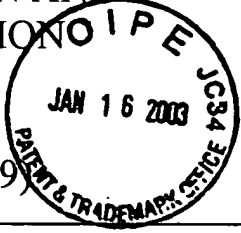
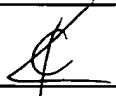







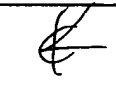

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




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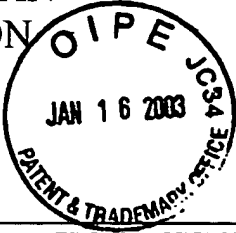










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| <b>INFORMATION DISCLOSURE<br/>CITATION IN AN<br/>APPLICATION</b><br><br>(PTO-1449)                                                                                                                                                                                                    |            |      |         | ATTY. DOCKET NO.<br><b>49657-961</b>    |          | SERIAL NO.<br><b>09/769,490</b> |    |
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| <b>U.S. PATENT DOCUMENTS</b>                                                                                                                                                                                                                                                          |            |      |         |                                         |          |                                 |    |
| EXAMINER'S<br>INITIALS                                                                                                                                                                                                                                                                | PATENT NO. | DATE | NAME    | CLASS                                   | SUBCLASS | FILING DATE                     |    |
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| <b>FOREIGN PATENT DOCUMENTS</b>                                                                                                                                                                                                                                                       |            |      |         |                                         |          |                                 |    |
| EXAMINER'S<br>INITIALS                                                                                                                                                                                                                                                                | PATENT NO. | DATE | COUNTRY | CLASS                                   | SUBCLASS | Translation                     |    |
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| <b>INFORMATION DISCLOSURE<br/>CITATION IN AN<br/>APPLICATION</b><br><br><b>(PTO-1449)</b>                                                                                                                                                       |            |      |         | ATTY. DOCKET NO.<br><b>49657-961</b>    |          | SERIAL NO.<br><b>09/769,490</b> |    |
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| <b>U.S. PATENT DOCUMENTS</b>                                                                                                                                                                                                                    |            |      |         |                                         |          |                                 |    |
| EXAMINER'S<br>INITIALS                                                                                                                                                                                                                          | PATENT NO. | DATE | NAME    | CLASS                                   | SUBCLASS | FILING DATE                     |    |
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| <b>FOREIGN PATENT DOCUMENTS</b>                                                                                                                                                                                                                 |            |      |         |                                         |          |                                 |    |
| EXAMINER'S<br>INITIALS                                                                                                                                                                                                                          | PATENT NO. | DATE | COUNTRY | CLASS                                   | SUBCLASS | Translation                     |    |
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.


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| <b>INFORMATION DISCLOSURE<br/>CITATION IN AN<br/>APPLICATION</b><br><br>(PTO-1449)                  |                                                                                                                                                                                                                                                                                                                                                           |      |         | ATTY. DOCKET NO.<br><b>49657-961</b>    |          | SERIAL NO.<br><b>09/769,490</b> |    |
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